

ABSTRACT OF THE DISCLOSURE

A method and system to form a refractory metal layer on a substrate features

10 nucleating a substrate using sequential deposition techniques in which the substrate is serially exposed to first and second reactive gases followed by forming a layer, employing vapor deposition, to subject the nucleation layer to a bulk deposition of a compound contained in one of the first and second reactive gases.

Figure 10: The β -dependence of the β -functions of the couplings α_s and α_{eff} for the $\overline{\text{MS}}$ scheme. The β -functions are calculated at the two-loop order. The β -function of α_s is shown in the left panel, and the β -function of α_{eff} is shown in the right panel. The β -functions are calculated for the $\overline{\text{MS}}$ scheme. The β -function of α_s is shown in the left panel, and the β -function of α_{eff} is shown in the right panel. The β -functions are calculated for the $\overline{\text{MS}}$ scheme.